Innovative Solution to Poor Target Utilization

- 60% Target Utilization Guaranteed*
- Excellent Deposition Film Properties
- Compact, Easily Retrofittable Design
- Extended Production Runs
- Scalable Design

* Patent Pending

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Localized target wear is eliminated by bidirectional movements of the magnet assembly.

- 60% Target Utilization
- Excellent Deposition Uniformity
- Simple, Rugged Mechanism
- Wear Optimized by Simple Computer Simulation

Advanced Magnetics:
- > 1100 Gauss at Target Surfaces
- Superior Film Quality
- Consistent Run-to-Run Film Properties

Economic Target Tiles:
- Simple Target Tile Design:
  - Easy to manufacture
  - No target bonding required
- Precious Metals (Costly Target Materials)
- Enables Quick Target Changes

Many Benefits:
- Reduced Cost of Ownership:
  - Decreased material costs
  - Minimized downtime
- Extended Production Runs
  - Less frequent target replacement
- Low Maintenance
- Compact Form Factor
  - Easy retrofits into existing tools
- Scalable Design

Typical Applications:
- Ceramic ITO Sputtering
- Rare and Precious Target Materials

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